

PRINTER RUSH

(PTO ASSISTANCE)

Application : <u>10532550</u>	Examiner : <u>Falano</u>	GAU : <u>1794</u>
From: <u>J. Blach</u>	Location: <u>IDC</u> FMF FDC	Date: <u>7/1/08</u>
Tracking #: <u>epm10532550</u>		Week Date: <u>07/01/08</u>

DOC CODE	DOC DATE	MISCELLANEOUS
<input type="checkbox"/> 1449		<input type="checkbox"/> Continuing Data
<input checked="" type="checkbox"/> IDS	<u>8/1/05</u>	<input type="checkbox"/> Foreign Priority
<input type="checkbox"/> CLM		<input type="checkbox"/> Document Legibility
<input type="checkbox"/> IIFW/FWCLM		<input type="checkbox"/> Fees
<input type="checkbox"/> SRFW		<input type="checkbox"/> Other
<input type="checkbox"/> DRW		
<input type="checkbox"/> OATH		
<input type="checkbox"/> 312		
<input type="checkbox"/> SPEC		

[RUSH] MESSAGE: _____

Please initial line through citations (last page).

Thank you!

[XRUSH] RESPONSE: _____

OK

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EXAMINER: PUBS contacts -- for DESIGNS: Don Fairchild, 703-308-9250 x126; for ALL OTHER FILES:
Bernadette Queen, 703-308-9250 x121

NOTE: This form will be included as part of the official USPTO record, with the Response document
coded as XRUSH.

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>	Docket number (Optional) 16169.6	Application Number 10/532,550
	Applicant(s) Ishii, et al.	
	Filing Date 4/22/2005	Group Art Unit Not Yet Assigned

* Examiner Initial	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
/LF/	U.S. Patent Application No. 10/532,564 entitled "GLASS SUBSTRATE FOR INFORMATION RECORDING MEDIUM AND METHOD FOR MANUFACTURING SAME," filed April 22, 2005.
/LF/	U.S. Patent Application No. 10/532,538 entitled "GLASS SUBSTRATE FOR INFORMATION RECORDING MEDIUM AND METHOD FOR MANUFACTURING SAME," filed April 22, 2005.

EXAMINER /Louis Falasco/	DATE CONSIDERED 2/2/2007
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.